
Computational Microelectronics L7 (Pre-recorded)

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1D nonlinear Poisson equation

Poisson equation

- Source-free Poisson equation

- When the net charge density vanishes, we have a special form of the Poisson equation:

$$\nabla \cdot [\epsilon(\mathbf{r}) \nabla \phi] = 0$$

- Now we want to keep the net charge density.

$$\nabla \cdot [\epsilon(\mathbf{r}) \nabla \phi] = -\rho(\mathbf{r})$$

- Charges inside semiconductor

$$\rho(\mathbf{r}) = qp(\mathbf{r}) - qn(\mathbf{r}) + qN_{dop}^+(\mathbf{r})$$

- Hole density, $p(\mathbf{r})$
- Electron density, $n(\mathbf{r})$
- Doping density, $N_{dop}^+(\mathbf{r})$: Positive for donors and negative for acceptors

At equilibrium,

- We have special expressions for charge densities:

- Hole density, $p(\mathbf{r}) = n_{int}(\mathbf{r}) \exp\left(-\frac{q\phi(\mathbf{r})}{k_B T}\right)$

- Electron density, $n(\mathbf{r}) = n_{int}(\mathbf{r}) \exp\left(\frac{q\phi(\mathbf{r})}{k_B T}\right)$

- By adopting these expressions, we have the nonlinear Poisson equation:

$$\nabla \cdot [\epsilon(\mathbf{r}) \nabla \phi] + q n_{int}(\mathbf{r}) \exp\left(-\frac{\phi(\mathbf{r})}{V_T}\right) - q n_{int}(\mathbf{r}) \exp\left(\frac{\phi(\mathbf{r})}{V_T}\right) + q N_{dop}^+(\mathbf{r}) = 0$$

Discretization

- When the nonlinear Poisson equation is considered,

- We have additional terms related to $\int_{x_{i-0.5}}^{x_{i+0.5}} \rho(\mathbf{r}) dx$.

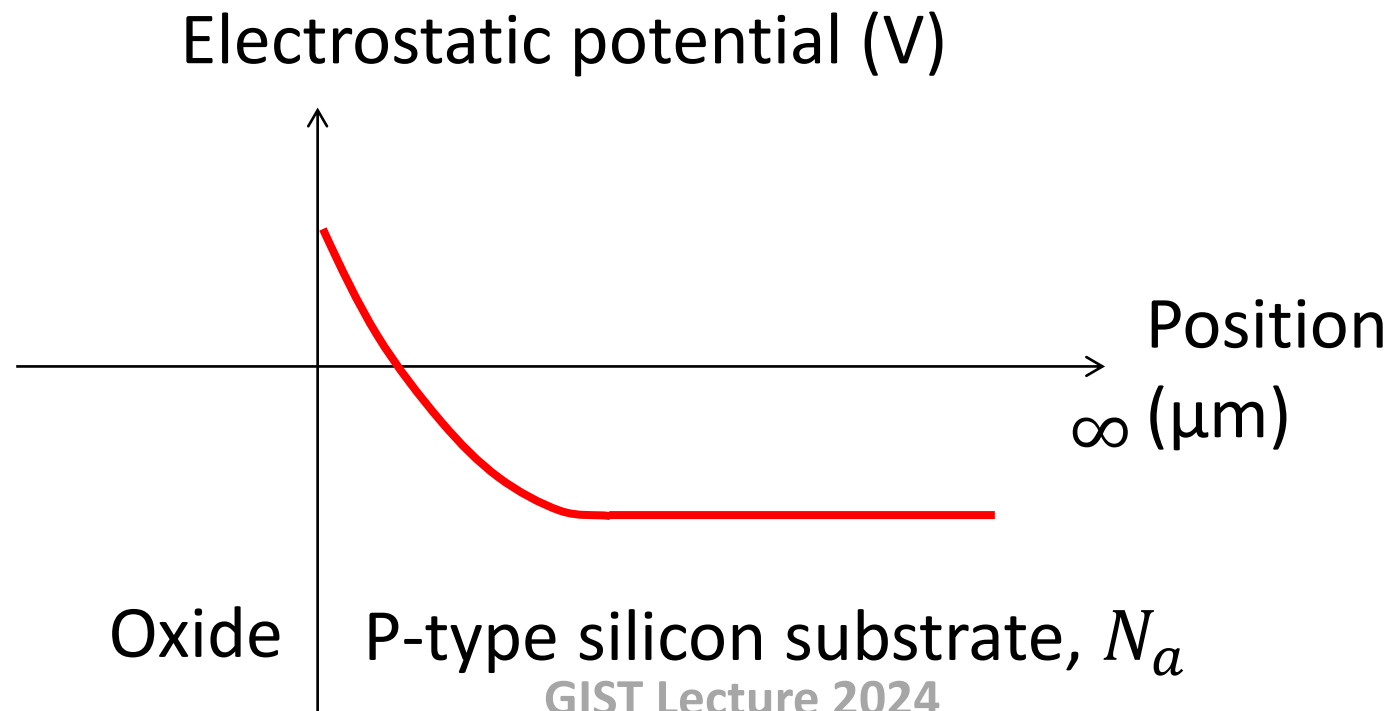
- Simple treatment for this integration:

$$\epsilon(x_{i+0.5}) \frac{\phi(x_{i+1}) - \phi(x_i)}{x_{i+1} - x_i} - \epsilon(x_{i-0.5}) \frac{\phi(x_i) - \phi(x_{i-1})}{x_i - x_{i-1}} + q \left(n_{int} \exp\left(-\frac{q\phi(x_i)}{k_B T}\right) - n_{int} \exp\left(\frac{q\phi(x_i)}{k_B T}\right) + N_{dop}^+(x_i) \right) (x_{i+0.5} - x_{i-0.5}) = 0$$

- This expression is used to construct the i -th row of b vector.

Only silicon region

- In general, we must consider the oxide layer and the gate contact.
 - For simplicity, consider only the silicon region.
 - It is assumed that the surface potential, $\phi_s = \phi(x = 0) - \phi_\infty$, is known.

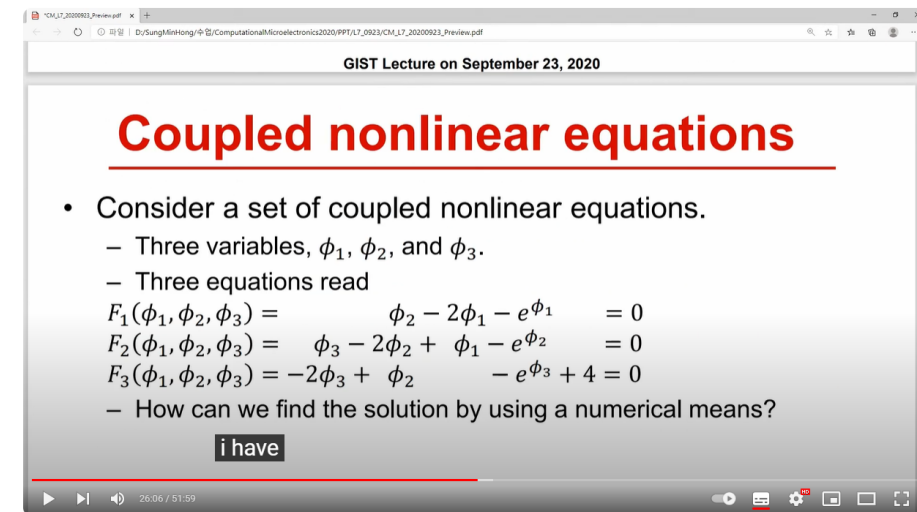


Once again, nonlinearity

- There are N unknown variables, $\phi_0, \phi_1, \dots, \phi_{N-1}$.
 - 1) Evaluate the following equation at $N - 2$ points, x_1, x_2, \dots, x_{N-2} .
$$\epsilon(x_{i+0.5}) \frac{\phi(x_{i+1}) - \phi(x_i)}{x_{i+1} - x_i} - \epsilon(x_{i-0.5}) \frac{\phi(x_i) - \phi(x_{i-1})}{x_i - x_{i-1}} + q \left(n_{int} \exp\left(-\frac{q\phi(x_i)}{k_B T}\right) - n_{int} \exp\left(\frac{q\phi(x_i)}{k_B T}\right) + N_{dop}^+(x_i) \right) (x_{i+0.5} - x_{i-0.5}) = 0$$
 - 2) Apply the boundary condition at 2 points, x_0 and x_{N-1} .
$$\begin{aligned}\phi_0 &= \phi_s + \phi_\infty \\ \phi_{N-1} &= \phi_\infty\end{aligned}$$
 - It is nonlinear!

Newton-Raphson method

- Newton method for multiple variables
 - For a single variable, ϕ , we calculate $f(\phi)$. Its derivative, $\frac{df}{d\phi}$, is useful.
 - For two variables, ϕ and ψ , we calculate $f(\phi, \psi)$ and $g(\phi, \psi)$. Partial derivatives are $\frac{\partial f}{\partial \phi}$, $\frac{\partial f}{\partial \psi}$, $\frac{\partial g}{\partial \phi}$, and $\frac{\partial g}{\partial \psi}$. How can we arrange them to calculate $\delta\phi$ and $\delta\psi$?
 - Watch my video [\[CM2020\] L6.5](#) from 26:06.
 - Key lesson:
 - Partial derivatives construct A.
 - Then, solve $Ax = b$.

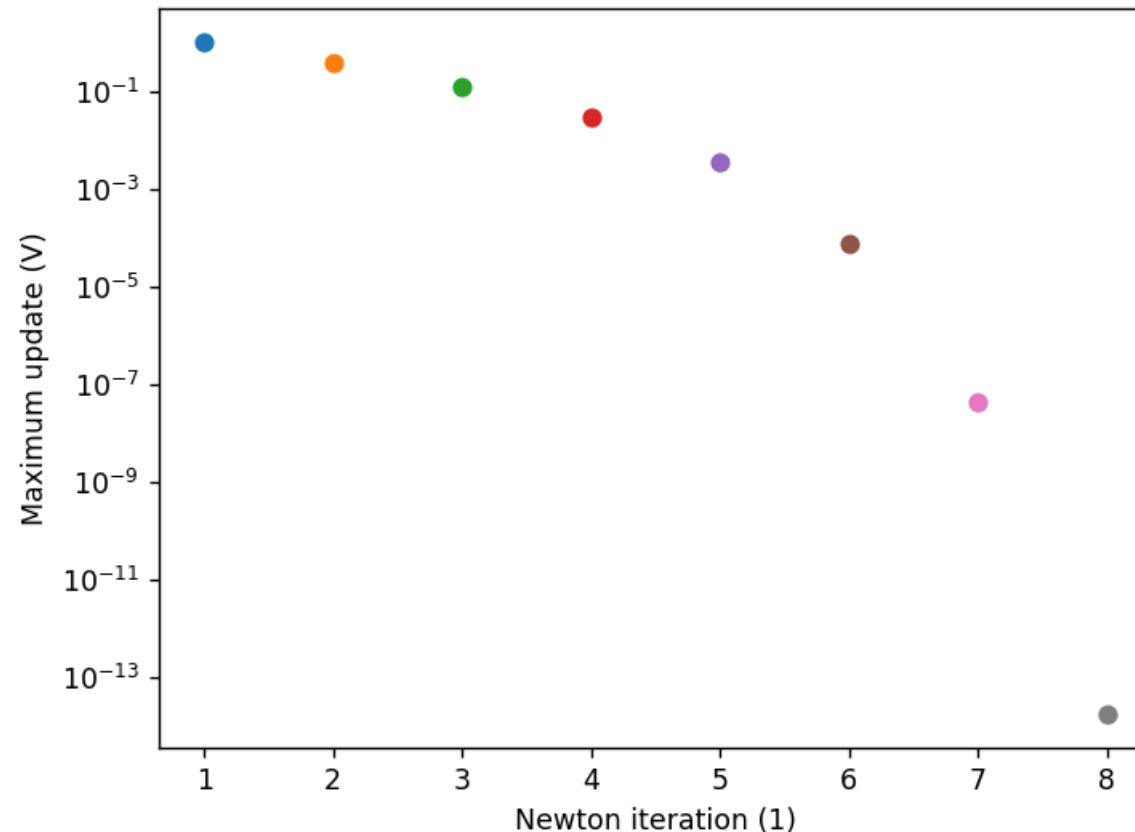


The i -th row

- Consider a case of $1 \leq i \leq N - 2$.
 - Then, $(i, i + 1)$ component becomes $\epsilon(x_{i+0.5}) \frac{1}{x_{i+1} - x_i}$.
 - The diagonal, (i, i) , component becomes
$$-\epsilon(x_{i+0.5}) \frac{1}{x_{i+1} - x_i} - \epsilon(x_{i-0.5}) \frac{1}{x_i - x_{i-1}} + q \left(-\frac{q}{k_B T} n_{int} \exp \left(-\frac{q\phi(x_i)}{k_B T} \right) - \frac{q}{k_B T} n_{int} \exp \left(\frac{q\phi(x_i)}{k_B T} \right) \right) (x_{i+0.5} - x_{i-0.5})$$
 - Also, $(i, i - 1)$ component becomes $\epsilon(x_{i-0.5}) \frac{1}{x_i - x_{i-1}}$.

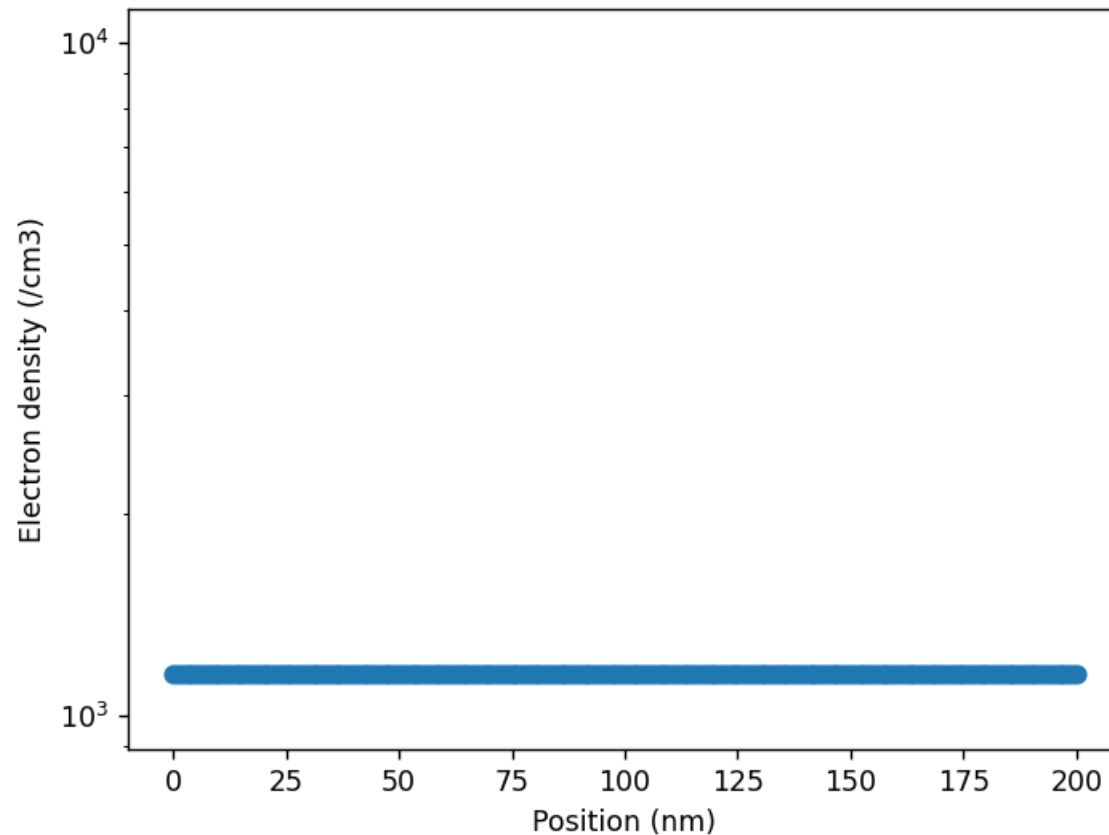
Convergence criterion

- By solving $Ax = b$, we obtain a vector of $\delta\phi$.
 - When every entry of this vector becomes sufficiently small, we can stop the Newton-Raphson iterations.



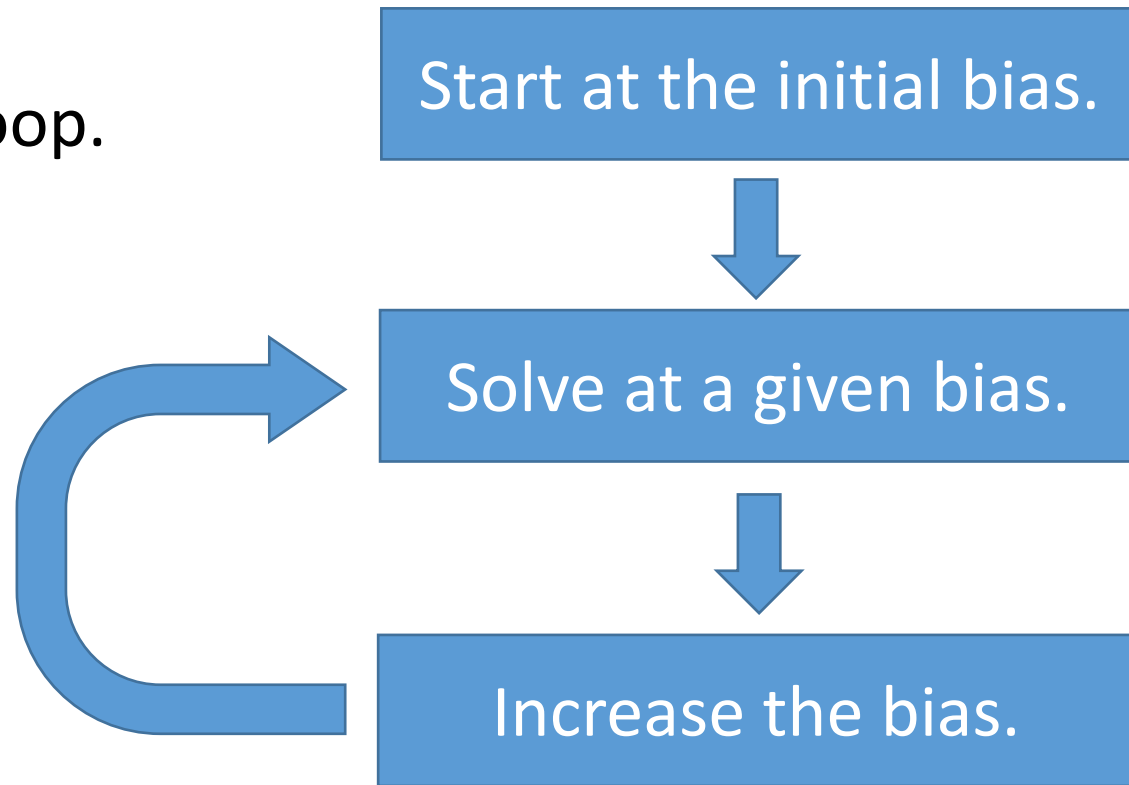
Flatband condition

- It means that $\phi_s = 0.0$ V.
 - Also, the p-type doping concentration is 10^{17} cm^{-3} .
 - Use $\Delta x = 1 \text{ nm}$. N is 201.



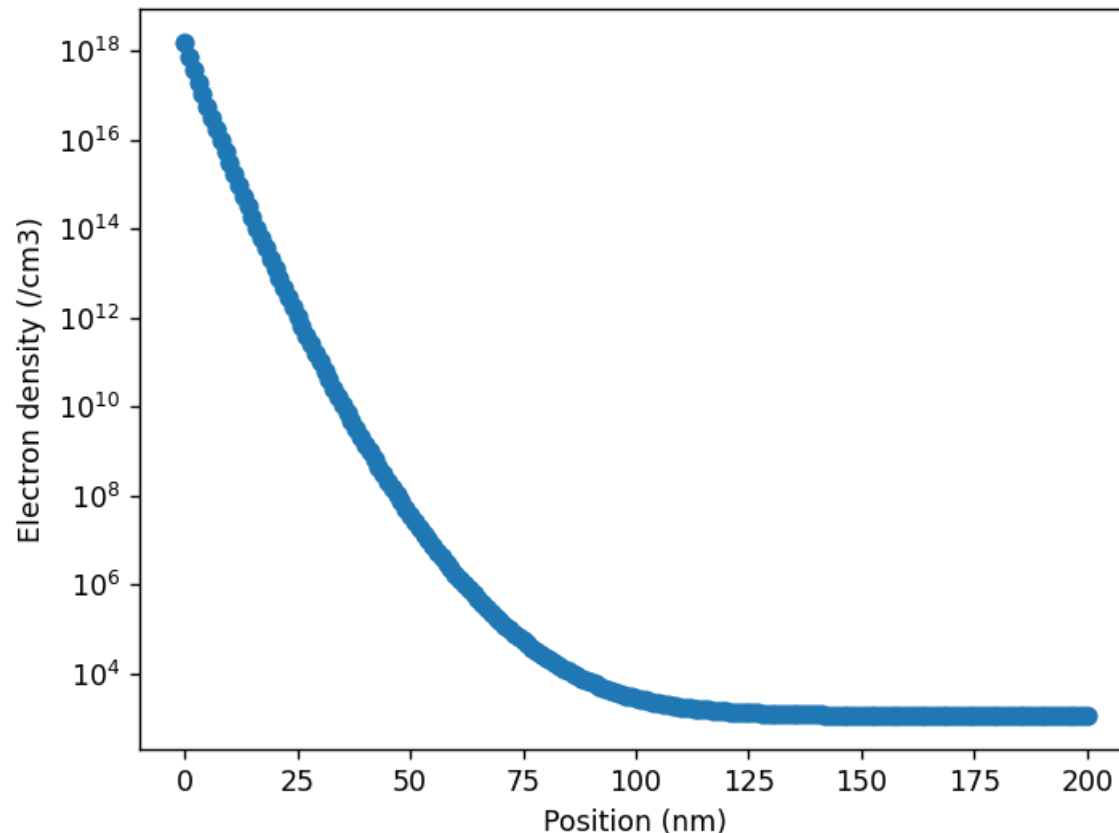
Bias ramping

- Ramp up the surface potential, ϕ_s . (The term, “bias,” is usually used for terminal quantities. In this lecture, we instead increase ϕ_s , only for simplicity.)
 - Simply add an outermost loop.



Electron density at $\phi_s = 0.9 \text{ V}$

- Now, strong inversion
 - The electron density at $x = 0$ is $1.5 \times 10^{18} \text{ cm}^{-3}$.
 - Numerically integrated electron density is $2.3 \times 10^{11} \text{ cm}^{-2}$.



Homework#7

- Due: AM08:00, October 8
- Problem#1
 - Now, we have two methods to calculate semiconductor charges. One is an analytic expression studied in L4. The other is a numerical approach studied in L7. When the p-type doping concentration is $4 \times 10^{17} \text{ cm}^{-3}$, compare two results.

Thank you for your attention!